

Electronic Supplementary Information (ESI)

**Surface Structure Evolution of Bimetallic Nickel Tungsten Nitride ($\text{Ni}_2\text{W}_3\text{N}$)
for High Performance Hydrogen Evolution**

Ji Young Hwang^a, Yeonju Park^b, Young Mee Jung^{*b}, Hyung-Kyu Lim^{*a}, Duck Hyun Youn^{*a}

^a Department of Chemical Engineering, Department of Integrative Engineering for Hydrogen Safety, Kangwon National University, Chuncheon 24341, South Korea.

^b Department of Chemistry, Institution for Molecular Science and Fusion Technology, Kangwon Radiation Convergence Research Support Center, Kangwon National University, Chuncheon, 24341, South Korea

*Corresponding authors

E-mail address: ymjung@kangwon.ac.kr (Y.M.J), hklim@kangwon.ac.kr (H.-K.L.), youndh@kangwon.ac.kr (D.H.Y.)

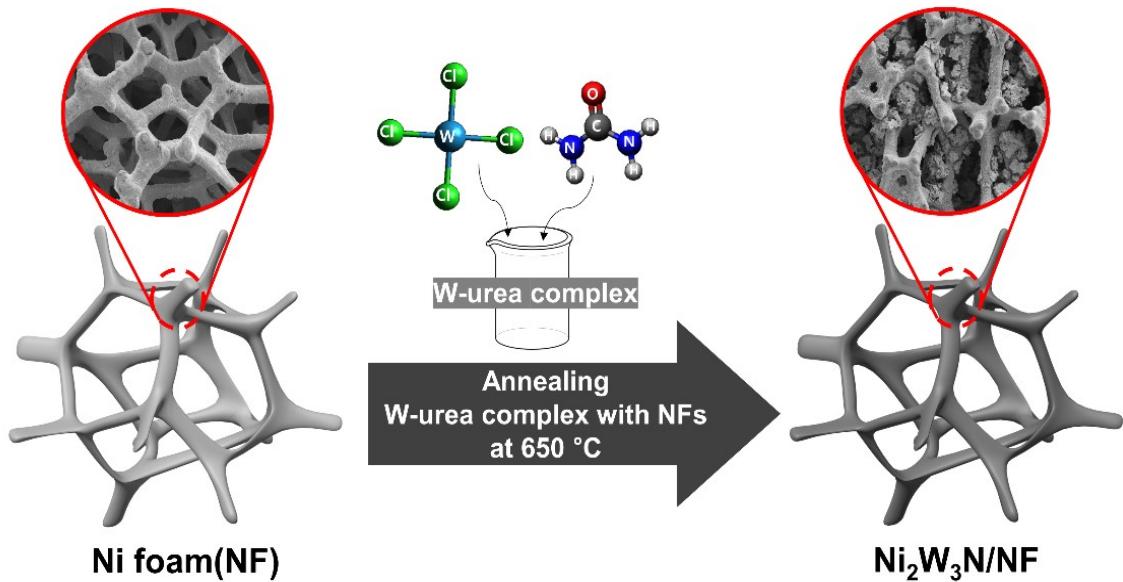


Fig. S1. Schematic illustration for synthetic method of Ni₂W₃N/NF.

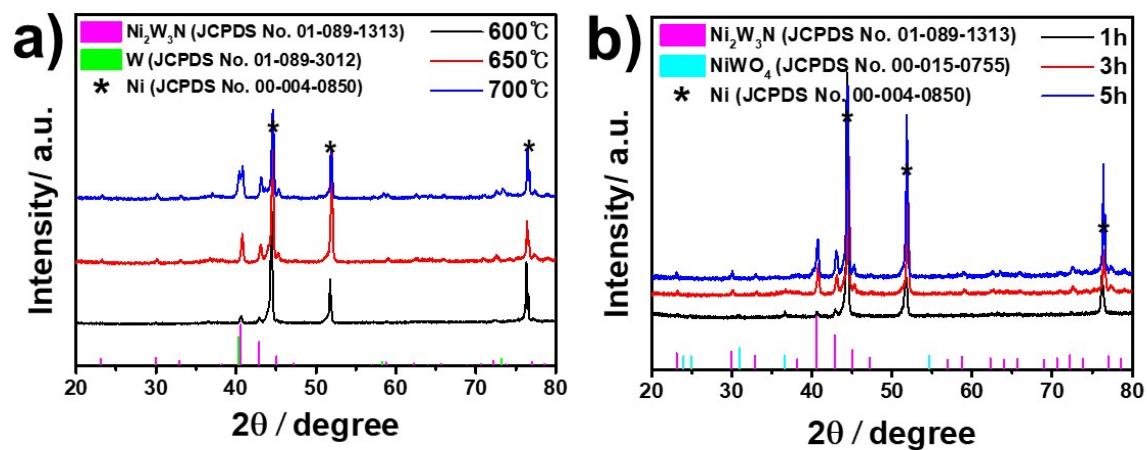


Fig. S2. XRD patterns of the prepared samples a) at different annealing temperatures (fixed duration: 3h) and b) at different annealing durations (fixed temperature: 650 °C).

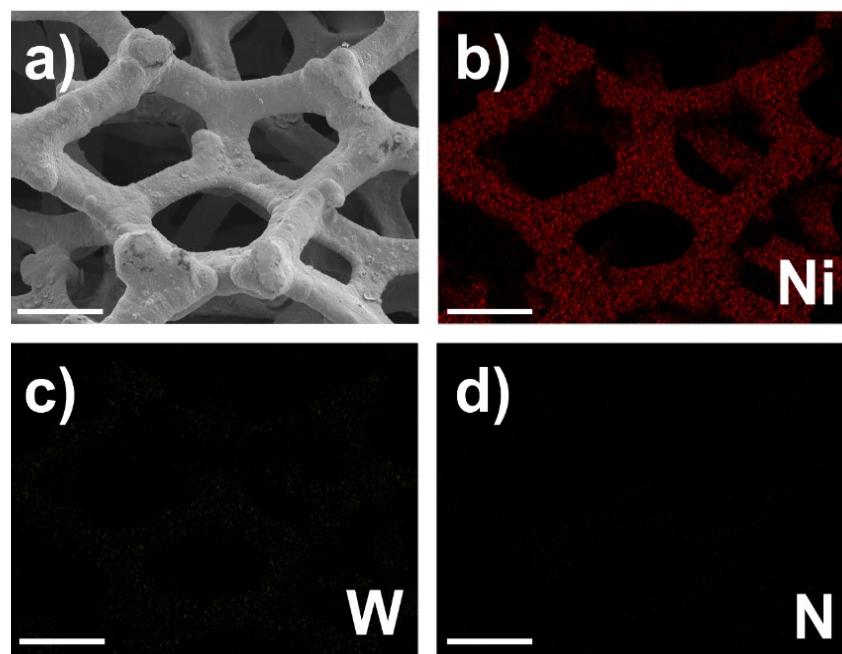


Fig. S3. (a) SEM images of NF and corresponding EDS mapping images of (b) Ni, (c) W, (d) N. Scale bars denote 200 μ m.

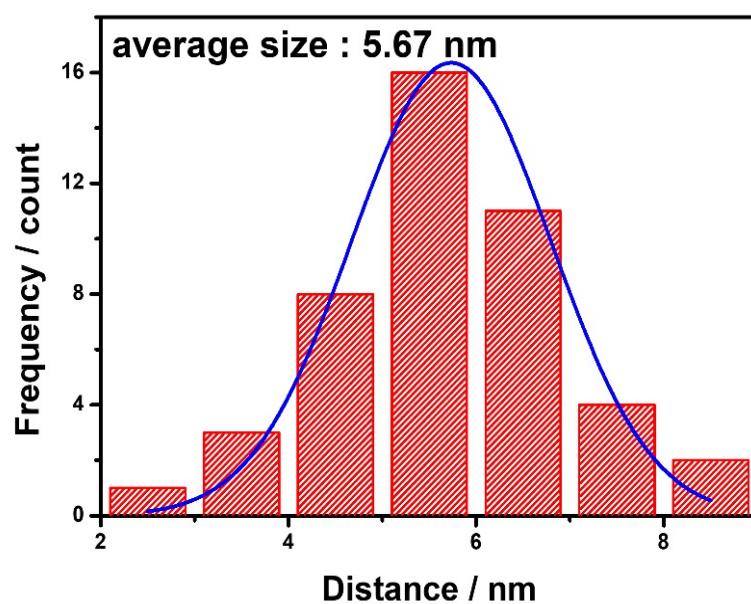


Fig. S4. Average particle size of $\text{Ni}_2\text{W}_3\text{N}/\text{NF}$.

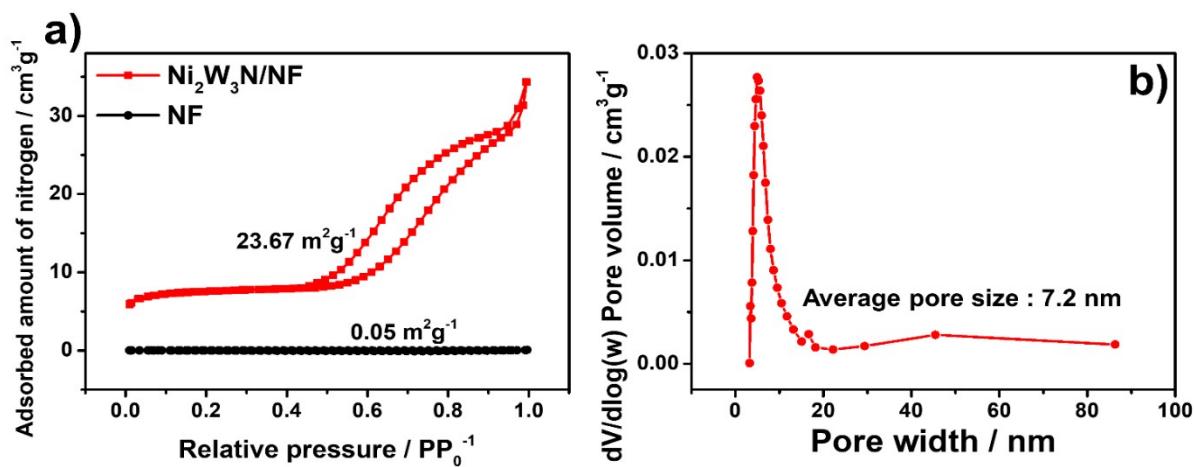


Fig. S5. (a) N₂ adsorption-desorption isotherms for Ni₂W₃N/NF and NF, (b) pore size distribution of Ni₂W₃N/NF.

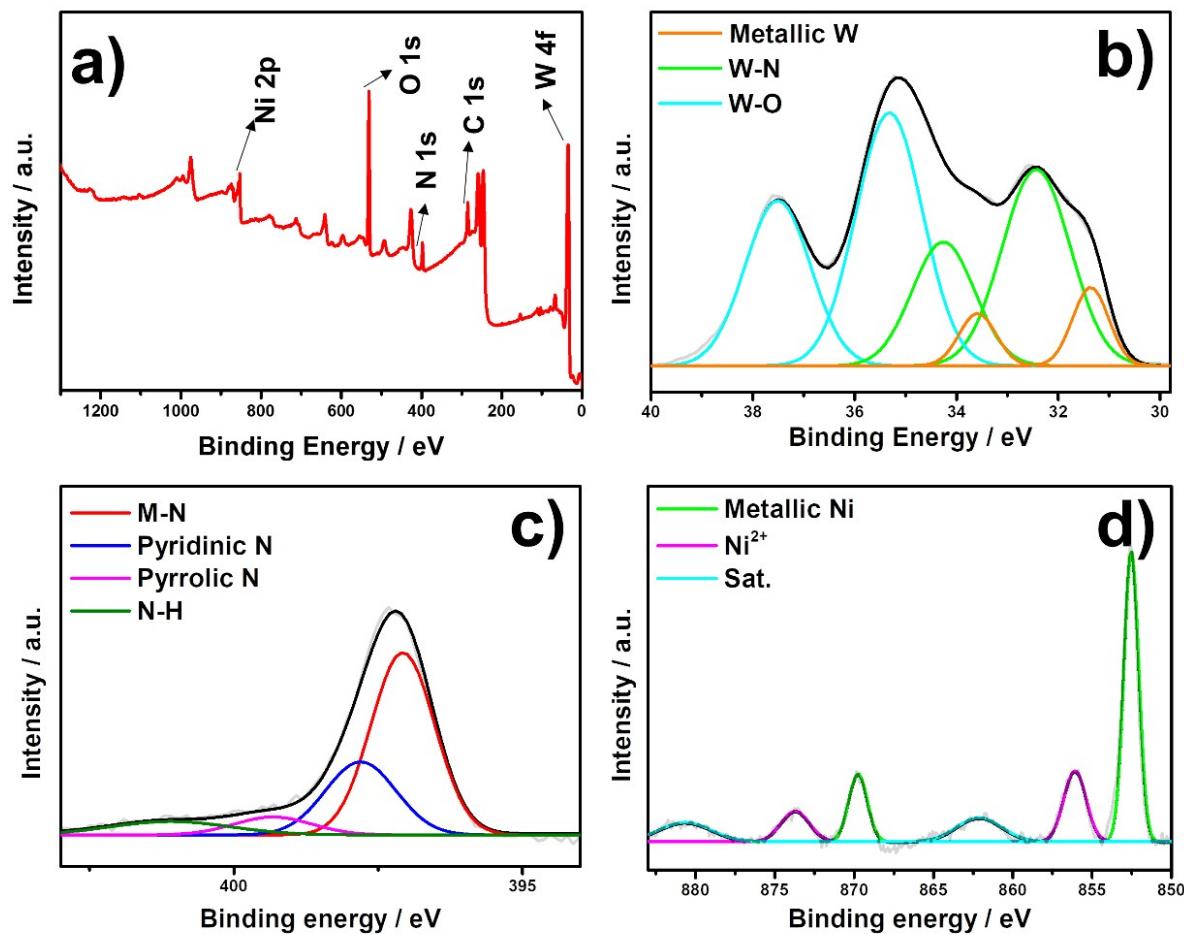


Fig. S6. XPS spectra of Ni₂W₃N/NF for (a) survey, (b) W 4f, (c) N 1s, and (d) Ni 2p.

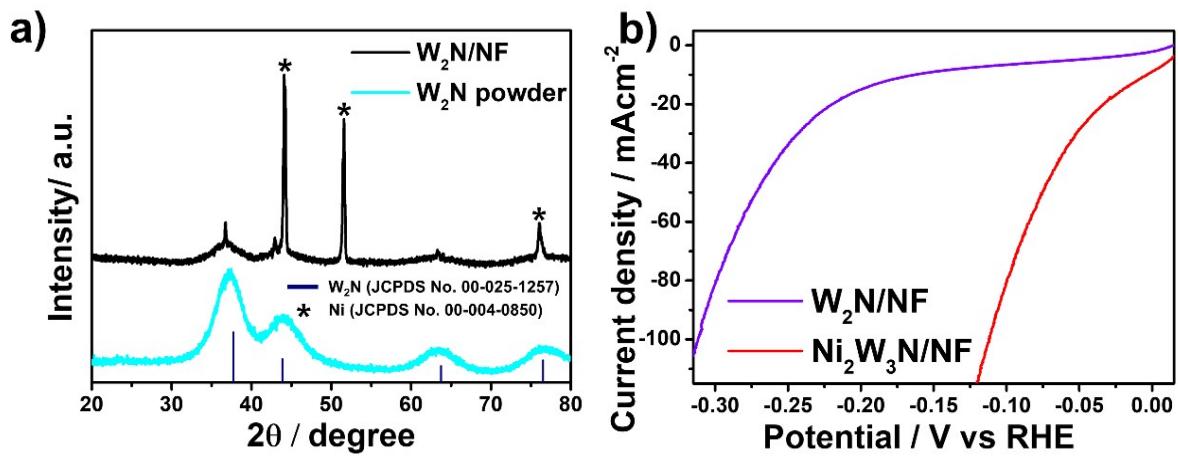


Fig. S7. (a) XRD patterns of W_2N powder and $\text{W}_2\text{N}/\text{NF}$. (b) The LSV curves of $\text{Ni}_2\text{W}_3\text{N}/\text{NF}$ and $\text{W}_2\text{N}/\text{NF}$.

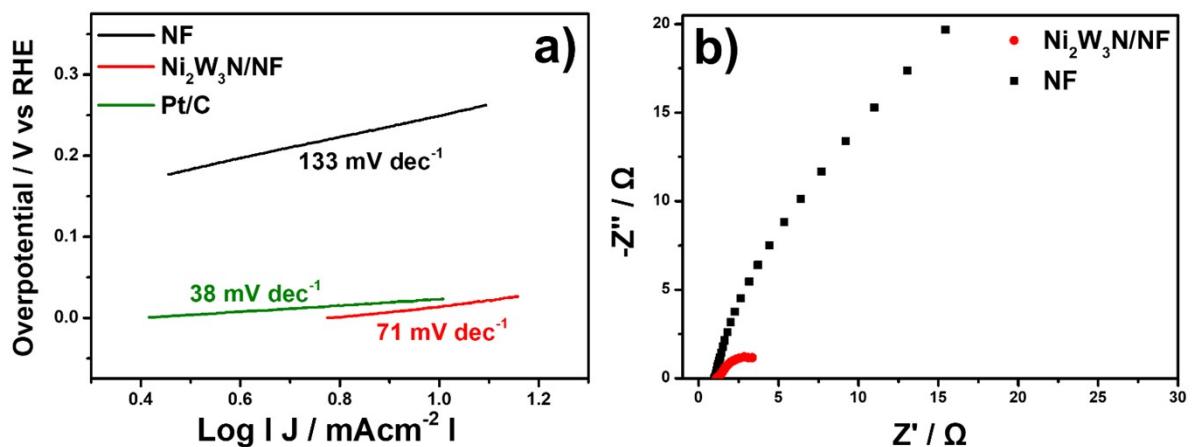


Fig. S8. (a) Tafel plots of $\text{Ni}_2\text{W}_3\text{N}/\text{NF}$, Pt/C, and NF. (b) Nyquist plots of $\text{Ni}_2\text{W}_3\text{N}/\text{NF}$ and NF.

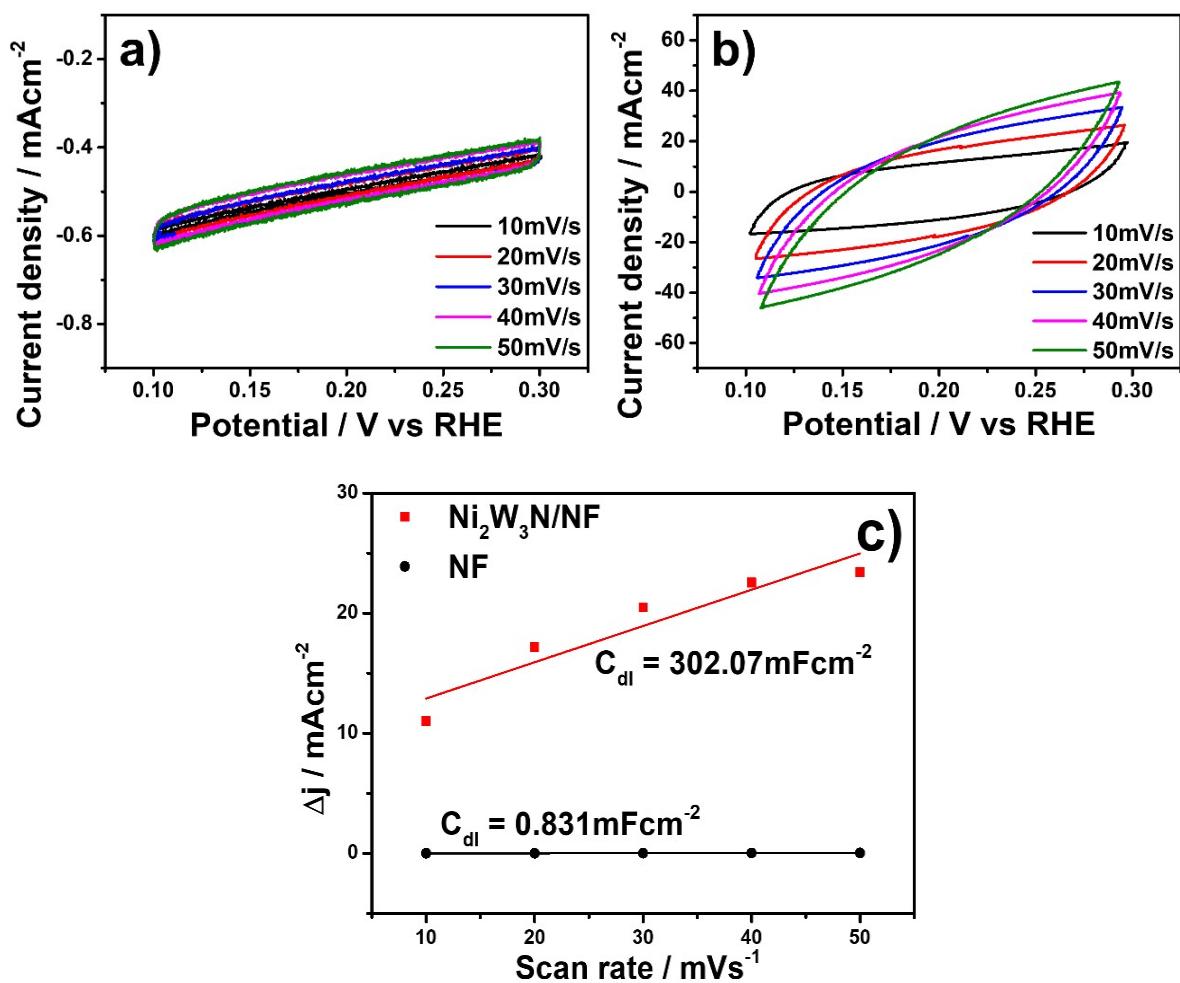


Fig. S9. Cyclic voltammograms of (a) NF and (b) Ni₂W₃N/NF at different scan rates. (c) measured capacitive current as a function of scan rate of Ni₂W₃N/NF, and NF.

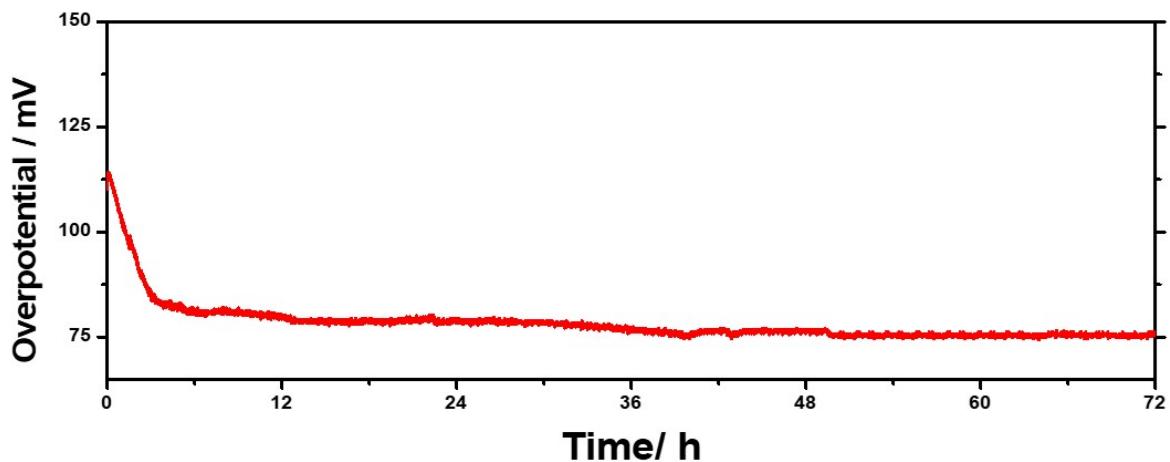


Fig. S10. Chronopotentiometric curve of $\text{Ni}_2\text{W}_3\text{N}/\text{NF}$ at 100 mA cm^{-2} for 72 h.

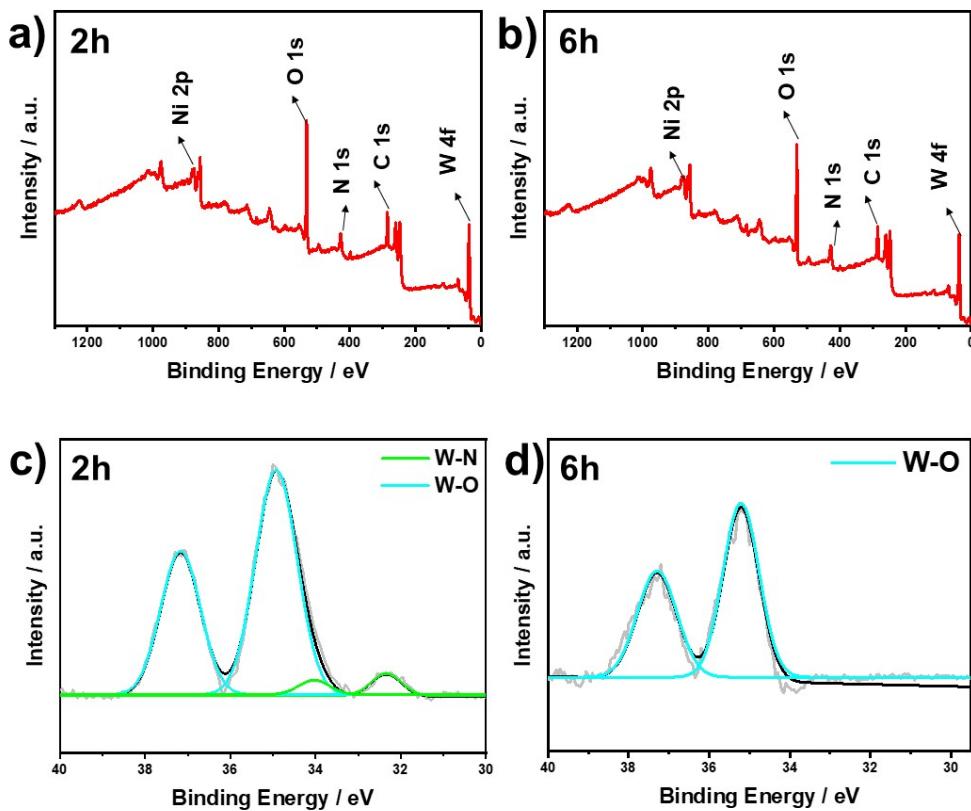


Fig. S11. XPS spectra of $\text{Ni}_2\text{W}_3\text{N}/\text{NF}$ during the stability test (a) survey scan for 2h, (b) survey scan for 6h, (c) W 4f for 2h, and (d) W 4f for 6h.

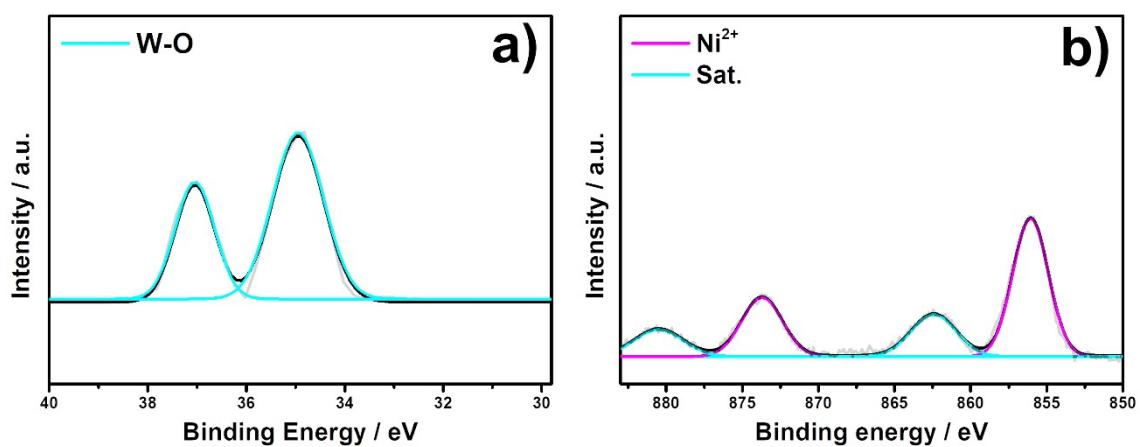


Fig. S12. XPS Spectra of after CP for 30 h of $\text{Ni}_2\text{W}_3\text{N}/\text{NF}$ for (a) W 4f, (b) Ni 2p.

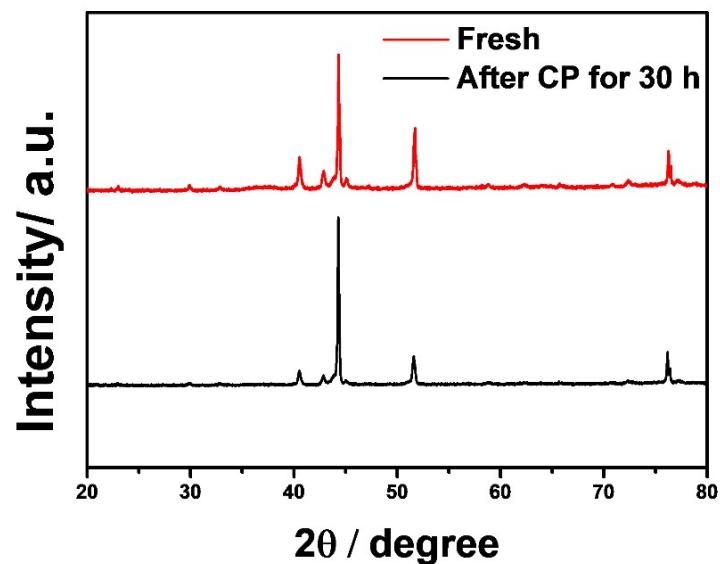


Fig. S13. XRD patterns of before and after CP for 30 h of $\text{Ni}_2\text{W}_3\text{N}/\text{NF}$.

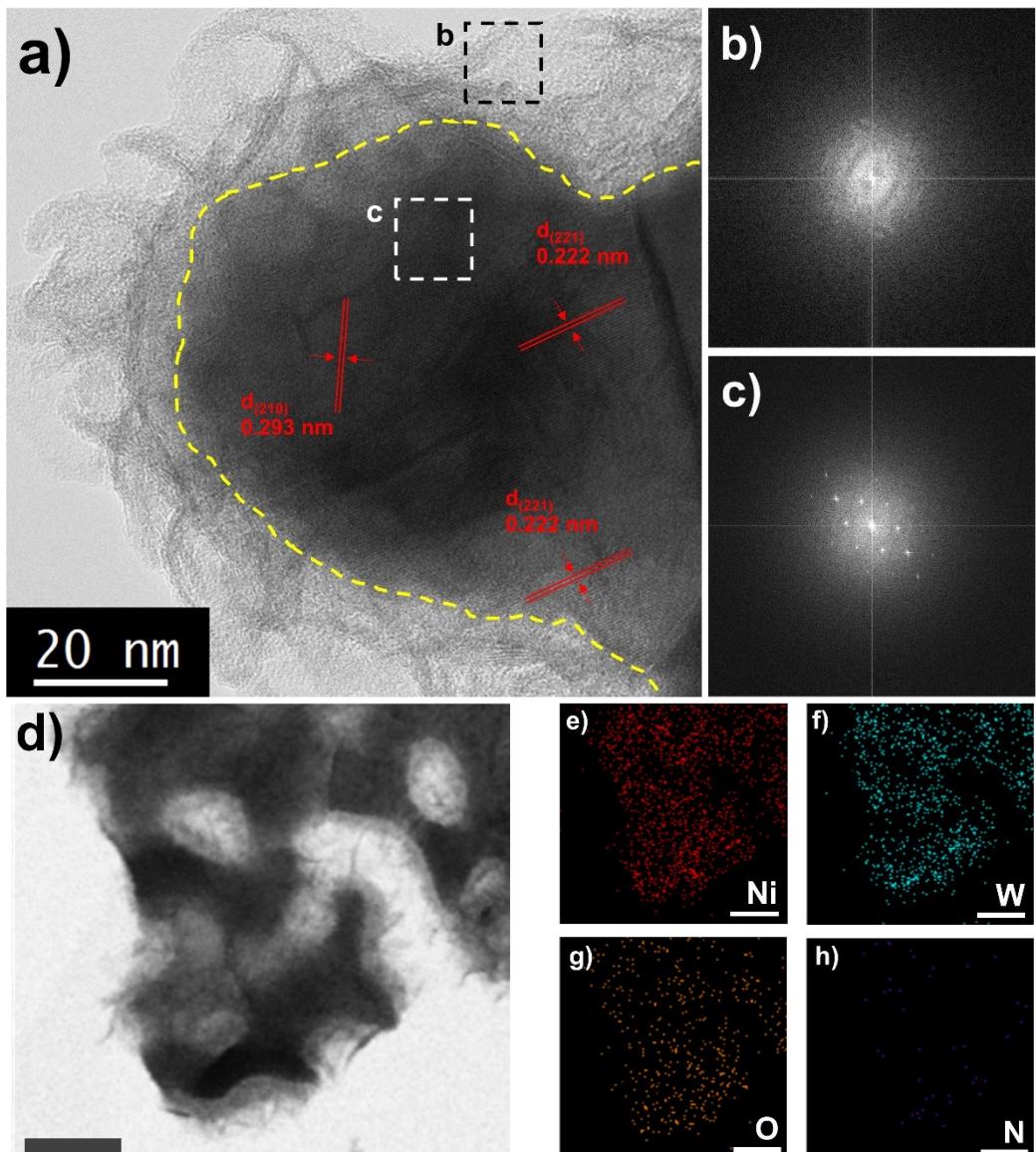


Fig. S14. (a) TEM image, (b), (c) FFT images, (d) HRTEM image (e) Ni, (f) W, (g) O, and (h) N.

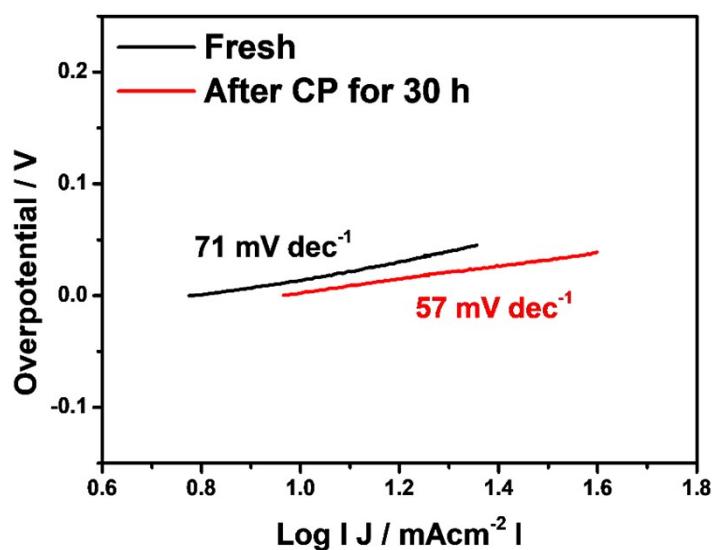


Fig. S15. Tafel plots of before and after CP for 30 h of $\text{Ni}_2\text{W}_3\text{N}/\text{NF}$.

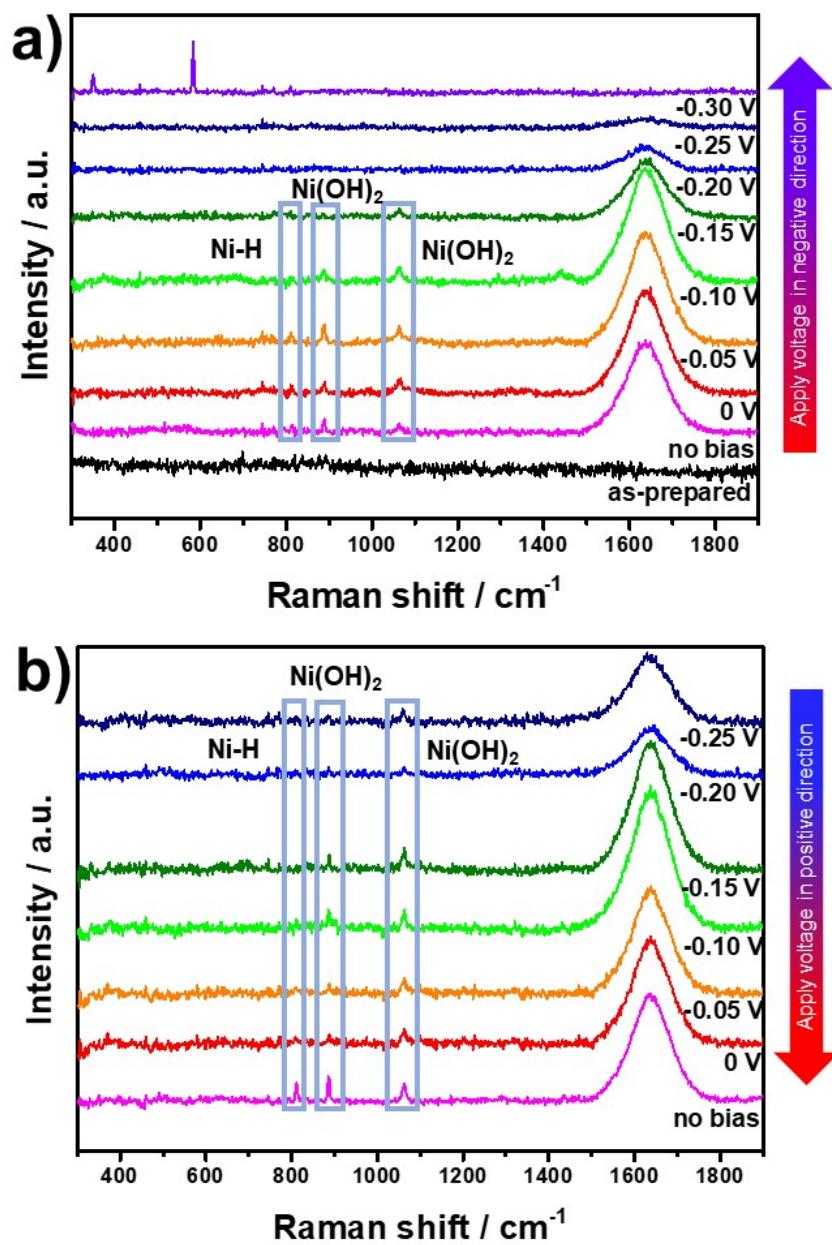


Fig. S16. Potential-dependent *in situ* Raman spectra of NF in 1 M KOH (a) applying voltage in the negative direction, and (b) applying voltage in the positive direction.

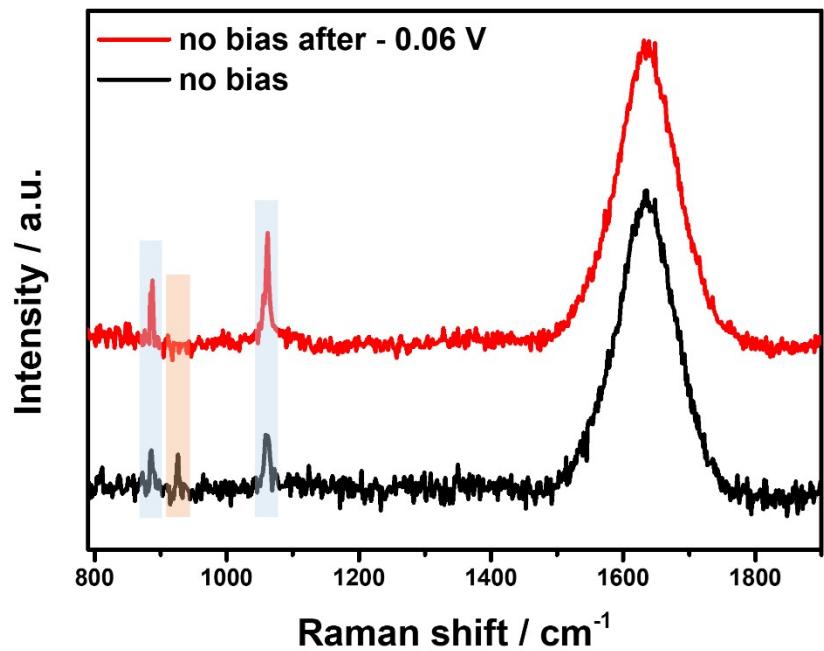


Fig. S17. The *ex-situ* Raman spectra of the no bias and after HER at -0.06 V of Ni₂W₃N/NF.

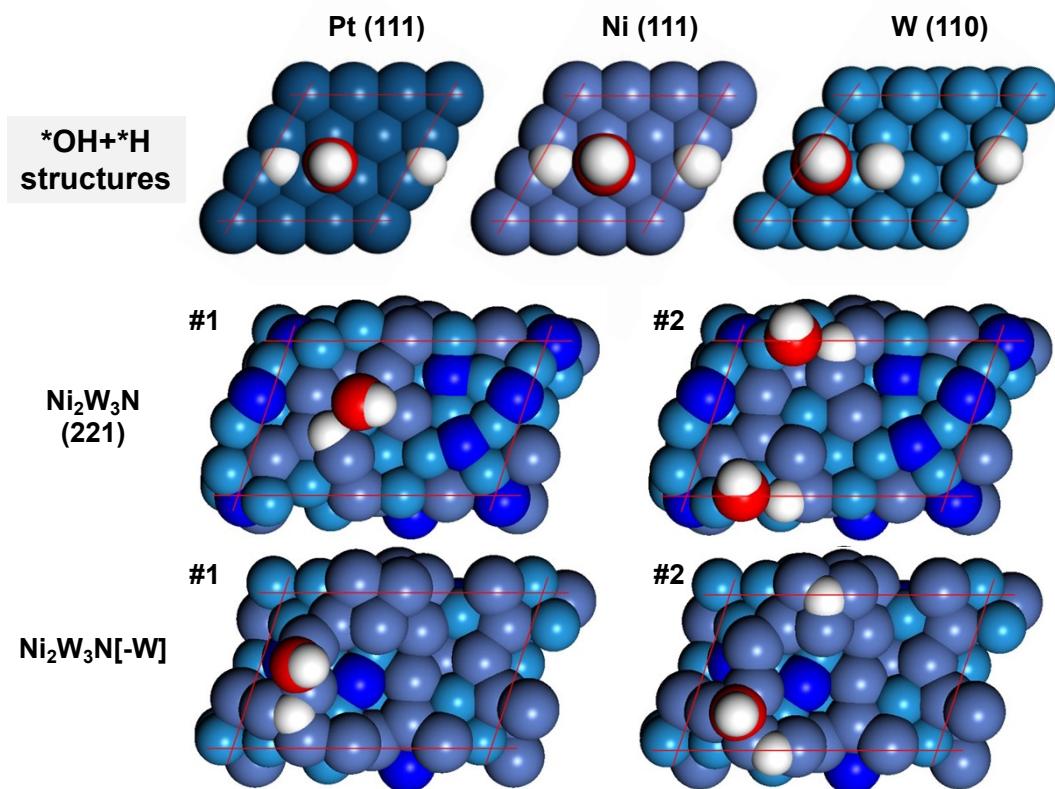


Fig. S18. Water dissociation structures on pure metal (Pt, Ni, W) and Ni₂W₃N surfaces.

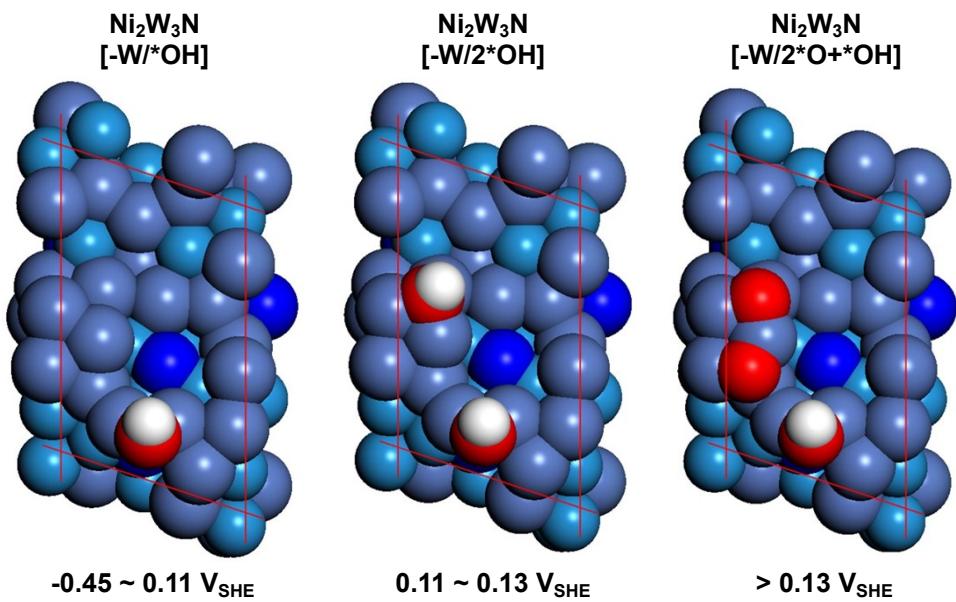


Fig. S19. The most stable surface functional groups on $\text{Ni}_2\text{W}_3\text{N}[-\text{W}]$ as a function of electrochemical potential.

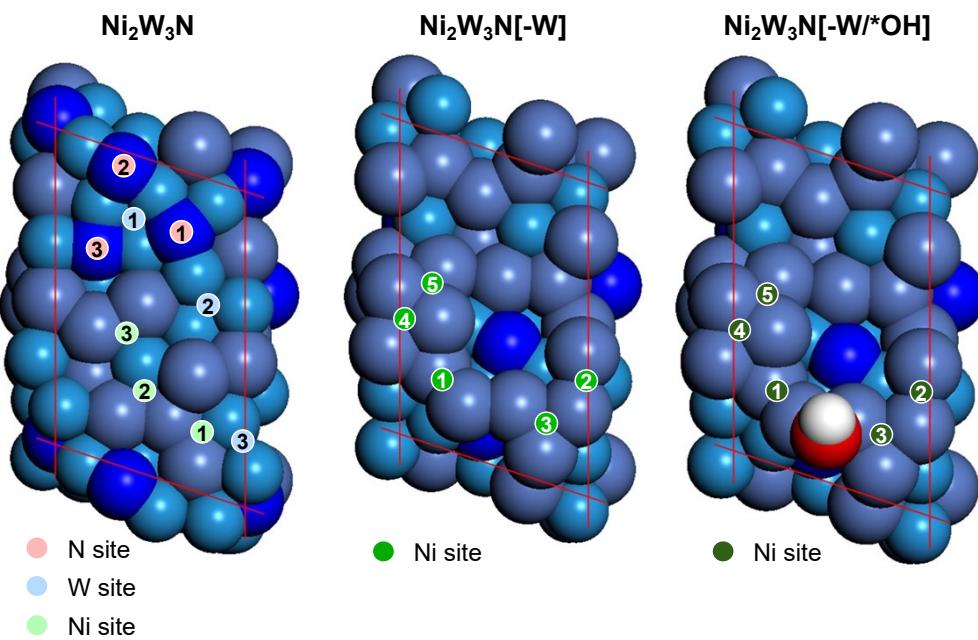
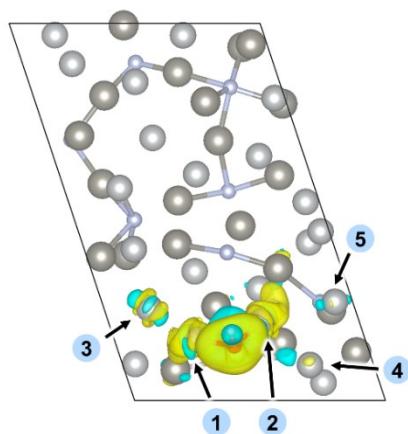
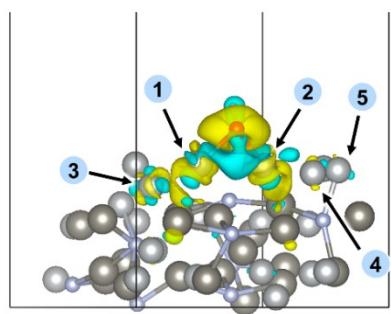


Fig. S20. Possible hydrogen binding sites for original $\text{Ni}_2\text{W}_3\text{N}(221)$, W-leached $\text{Ni}_2\text{W}_3\text{N}[-\text{W}]$, and $*\text{OH}$ -attached $\text{Ni}_2\text{W}_3\text{N}[-\text{W}/*\text{OH}]$ surfaces.

Differential charge density
 $\Delta\rho = \rho(^*\text{OH}) - \rho(^*) - \rho(\text{OH})$



**Bader partial charge
@ Ni (e)**

| # | * | *OH |
|---|-------|-------|
| 1 | -0.17 | +0.07 |
| 2 | -0.21 | +0.05 |
| 3 | -0.18 | -0.18 |
| 4 | -0.23 | -0.20 |
| 5 | +0.06 | +0.05 |

Fig. S21. Differential charge density iso-surface map of Ni₂W₃N[-W/*OH] surface and corresponding Bader partial charge analysis results. Adjacent Ni atoms (1 and 2) show significant electron depletion due to the electron-withdrawing effect of *OH.

Table S1. Comparison of the HER performance in alkaline media with reported bimetallic TMN-based catalysts.

| | electrolyte | η_{50} [mV] | η_{100} [mV] | Tafel slope [mV dec ⁻¹] | Reference |
|---|-------------|----------------------|-------------------|--|-----------|
| Ni ₂ W ₃ N/NF (Fresh) | 1 M KOH | 75.5 | 112 | 71 | This work |
| Ni ₂ W ₃ N/NF (After CP for 30h) | 1 M KOH | 46.5 | 78.7 | 57 | This work |
| Co ₃ Mo ₃ N/ Ni ₃ Mo ₃ N | 1 M KOH | 36 (η_{10}) | 130 | 53 | 1 |
| Ni ₃ FeN@C/NF | 1 M KOH | ~200 | 277 | 131 | 2 |
| NiMoN | 1 M KOH | 227 | 293 | 174 | 3 |
| Co-Mo-N/NF | 1 M KOH | 81 (η_{10}) | 198 | 121 | 4 |
| Ni ₃ Mo ₃ N-NC/NF | 1 M KOH | 39 (η_{10}) | 149 | 71 | 5 |
| NiMo _{0.75} N/PNCT | 1 M KOH | 52 (η_{10}) | ~200 | 82 | 6 |
| Co ₂ Ni ₁ N | 1 M KOH | ~200 | N/A | 60.17 | 7 |
| Ni ₂ Mo ₃ N/NF | 1 M KOH | 89 | 123.8 | 62 | 8 |
| FeNi ₃ N/NG | 1 M KOH | 98 (η_{20}) | 186 | 83.1 | 9 |
| NiMoN-550 | 1 M KOH | 159 (η_{20}) | 265 | 79 | 10 |
| CoMoN _x -400 NSAs/NF | 1 M KOH | 91 (η_{10}) | 208 | 70.3 | 11 |
| Co _{3.2} Fe _{0.8} N/NMC- 100 | 1 M KOH | 315 (η_{10}) | N/A | N/A | 12 |
| NiCo ₂ N/NF | 1 M KOH | ~180 (η_{10}) | N/A | 79 | 13 |
| NiT _x N _x | 1 M KOH | 125 (η_{10}) | ~200 | 71 | 14 |
| Ni ₂ Fe ₂ N/Ni ₃ Fe | 1 M KOH | 74 (η_{10}) | N/A | 53 | 15 |
| V-Ni ₂ Mo ₃ N | 1 M KOH | 54 (η_{10}) | 117 | 42.8 | 16 |
| MoVN | 1 M KOH | 108 (η_{10}) | ~180 | 60 | 17 |
| Cu _x Ni _{4-x} N/NF | 1 M KOH | 12 (η_{10}) | 111 | 86 | 18 |
| Ni ₃ Mo ₃ N/NF-2.0 | 1 M KOH | 28 (η_{10}) | N/A | 60 | 19 |
| Ni/Ni _{0.8} Mo _{4.2} N ₆ | 1 M KOH | 20 (η_{10}) | ~130 | 38 | 20 |
| Fe ₂ Ni ₂ N | 1 M KOH | 110 (η_{10}) | ~310 | 101 | 21 |

References

1. J. Tang, S. Zhang, Y. Zeng, B. Yang, K. Zhang, Y. Li, Y. Yao and J. Hu, *Chem. Eng. J.*, 2024, **487**, 150439.
2. B. Wang, M. Lu, D. Chen, Q. Zhang, W. Wang, Y. Kang, Z. Fang, G. Pang and S. Feng, *J. Mater. Chem. A*, 2021, **9**, 13562-13569.
3. V. Jayaraman, G. Jang, G.-H. Noh, M. Murmu and D.-H. Kim, *J. Mater. Chem. A*, 2024., doi: <https://doi.org/10.1039/D4TA01117A>
4. J. Zhu, Q. Du, M. A. Khan, H. Zhao, J. Fang, D. Ye and J. Zhang, *Appl. Surf. Sci.*, 2023, **623**, 156989.
5. P. Tan, Y. Wang, L. Yang, X. Zhang and J. Pan, *Diam. Relat. Mater.*, 2023, **136**, 109974.
6. B. Jiang, J. Li, Y. Cui, S. Shi, N. Jiang and J. Guan, *J. Alloys Compd.*, 2023, **958**, 170371.
7. X. Feng, H. Wang, X. Bo and L. Guo, *ACS Appl. Mater. Interfaces*, 2019, **11**, 8018-8024.
8. S. H. Park, T. H. Jo, M. H. Lee, K. Kawashima, C. B. Mullins, H.-K. Lim and D. H. Youn, *J. Mater. Chem. A*, 2021, **9**, 4945-4951.
9. L. Liu, F. Yan, K. Li, C. Zhu, Y. Xie, X. Zhang and Y. Chen, *J. Mater. Chem. A*, 2019, **7**, 1083-1091.
10. Z. Yin, Y. Sun, C. Zhu, C. Li, X. Zhang and Y. Chen, *J. Mater. Chem. A*, 2017, **5**, 13648-13658.
11. Y. Lu, Z. Li, Y. Xu, L. Tang, S. Xu, D. Li, J. Zhu and D. Jiang, *Chem. Eng. J.*, 2021, **411**, 128433.
12. K. Zhang, W. Mai, J. Li, G. Li, L. Tian and W. Hu, *ACS Appl. Nano Mater.*, 2019, **2**, 5931-5941.
13. Y. Wang, B. Zhang, W. Pan, H. Ma and J. Zhang, *ChemSusChem*, 2017, **10**, 4170-4177.
14. S. Tang, B. Ouyang, H. Tan, W. Zhou, Z. Ma and Y. Zhang, *Electrochim. Acta*, 2020, **362**, 137222.
15. Y. Hu, T. Xiong, M.-S. J. T. Balogun, Y. Huang, D. Adekoya, S. Zhang and Y. Tong, *Mater. Today Phys.*, 2020, **15**, 100267.
16. P. Zhou, X. Lv, Y. Gao, Z. Liang, Y. Liu, Z. Wang, P. Wang, Z. Zheng, Y. Dai and B. Huang, *Electrochim. Acta*, 2020, **337**, 135689.
17. B. Wei, G. Tang, H. Liang, Z. Qi, D. Zhang, W. Hu, H. Shen and Z. Wang, *Electrochim. Commun.*, 2018, **93**, 166-170.
18. Y. Ma, Z. He, Z. Wu, B. Zhang, Y. Zhang, S. Ding and C. Xiao, *J Mater. Chem. A*, 2017, **5**, 24850-24858.
19. Q. Zhang, H. Zhang, C. Lin, Z. Zhang, X. Zuo, Q. Yang, H. Tang and G. Li, *J. Electrochem. Soc.*, 2024, **171**, 053511.
20. S. Liang, H. Hu, J. Liu, H. Shen, Q. Li, N. Qiu, H. Guo, X. Guo, S. Du and Y. Zhu, *Appl. Catal. B: Environ.*, 2023, **337**, 123008.
21. M. Jiang, Y. Li, Z. Lu, X. Sun and X. Duan, *Inorg. Chem. Front.*, 2016, **3**, 630-634.